

# DEVELOPMENT OF A MINIATURE RECTILINEAR ION TRAP ARRAY WITH INDEPENDENTLY CONTROLLED CHANNELS

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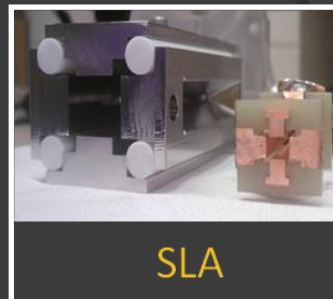
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# Mass analyzer miniaturization: Scale, RF, Fabrication Technologies, and Cost

- Complementary to miniaturization
- Fabrication of devices with complex geometries
- Cost effective (\$1500 vs. \$110)
- Manufacturing time (days vs. weeks)

$Y_0 = 1.33\text{mm}$

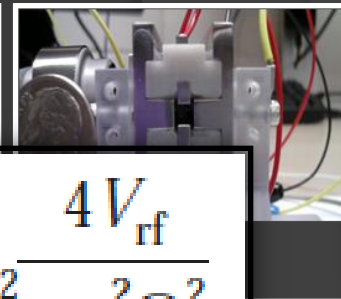
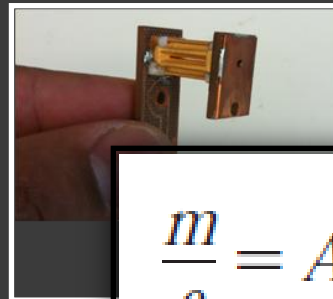
$X_0 = 1.66\text{mm}$



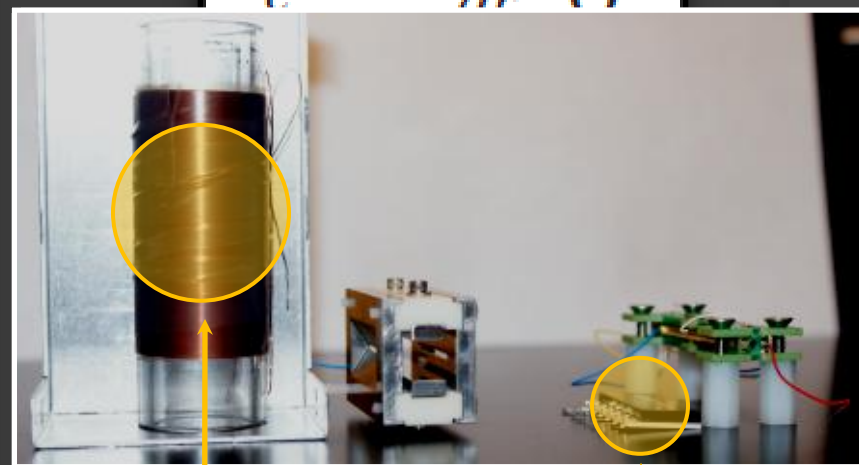
SLA



PCB



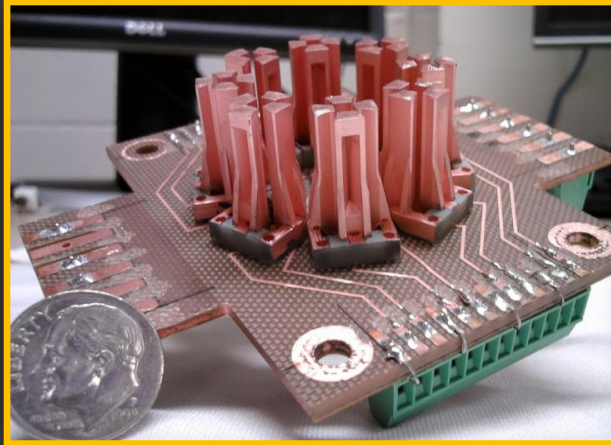
$$\frac{m}{e} = A_2 \frac{4V_{\text{rf}}}{\omega^2 \Omega^2}$$



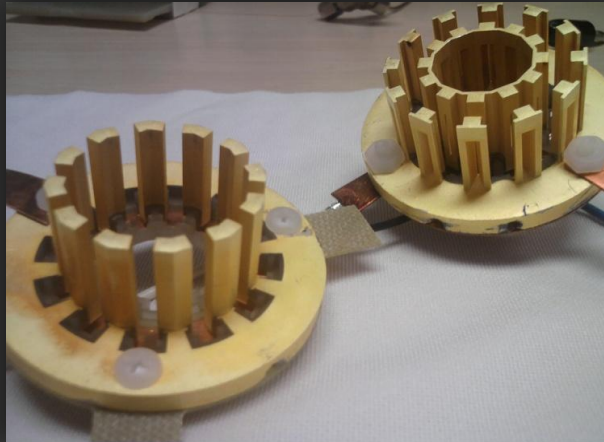
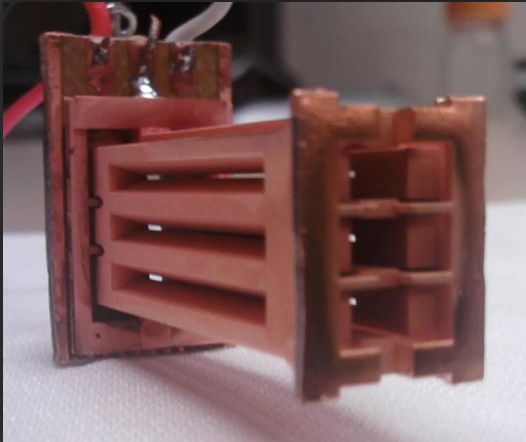
Large inductor  
for RF drive

Small amplifier  
for RF drive

# Arrays offset the effect of ion attenuation due to miniaturization



- Fabrication Technology: Stereolithography apparatus
- multiple RITs for increased ion capacity
- Geometrically complex electrode structures
  - Circular
  - Linear
- Fabrication flexibility
  - Monolithic construction
  - Independently isolated electrodes





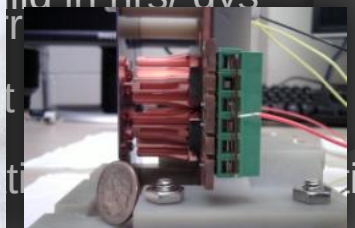
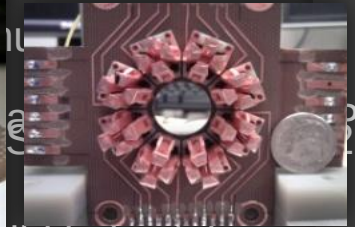
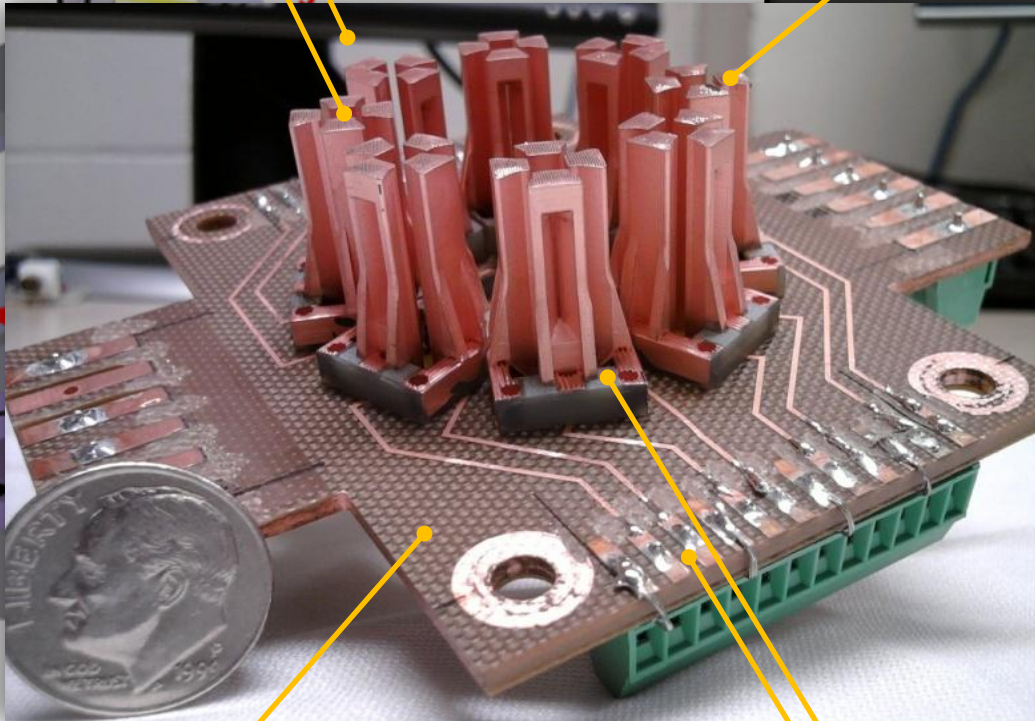
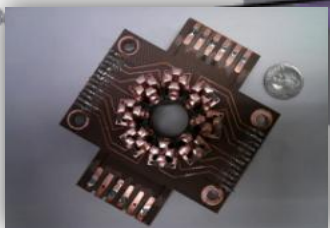
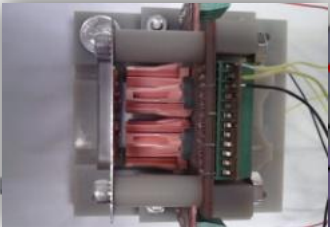
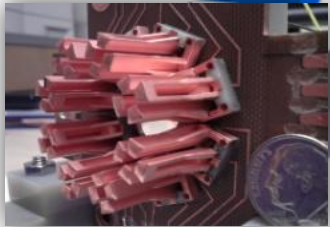
# Stereolithography Apparatus (SLA) Fabrication

Trapping dimensions:

Analyzer footprint:

Base PCB substrate  
Viper si2 SLA system

8 independent mass analyzers

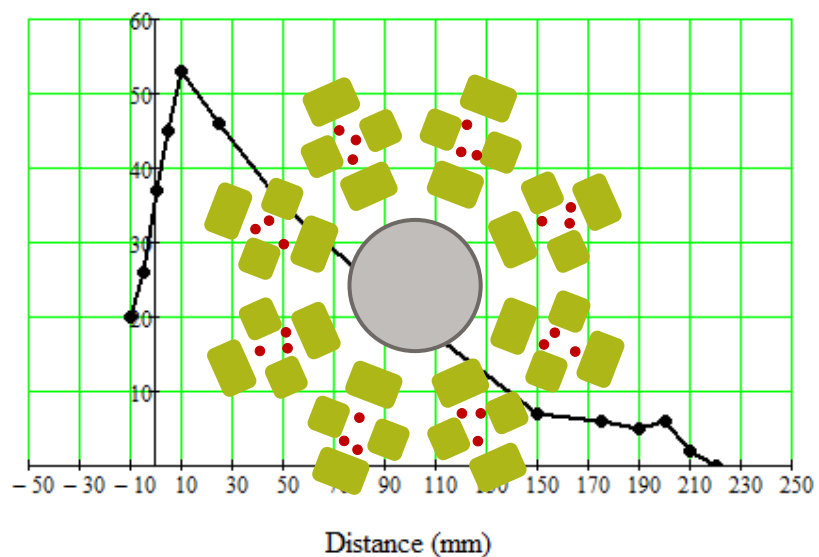
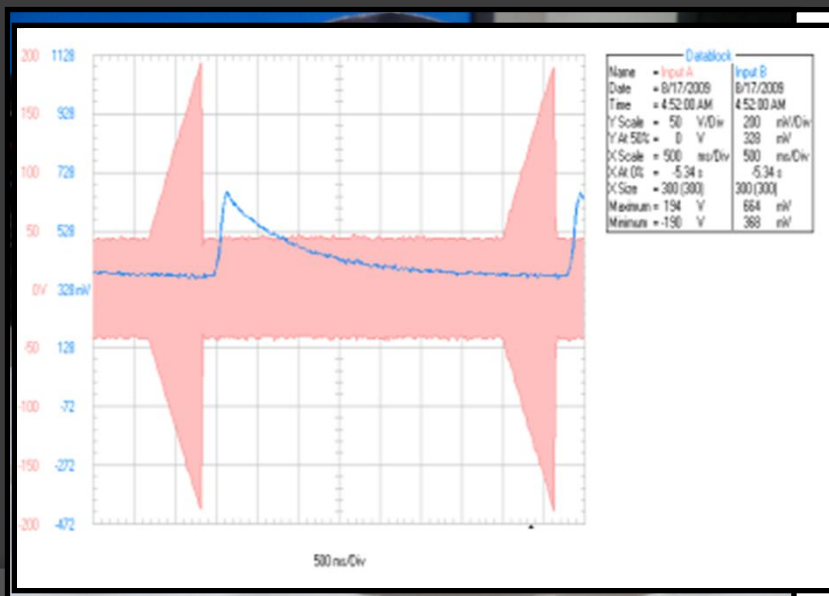
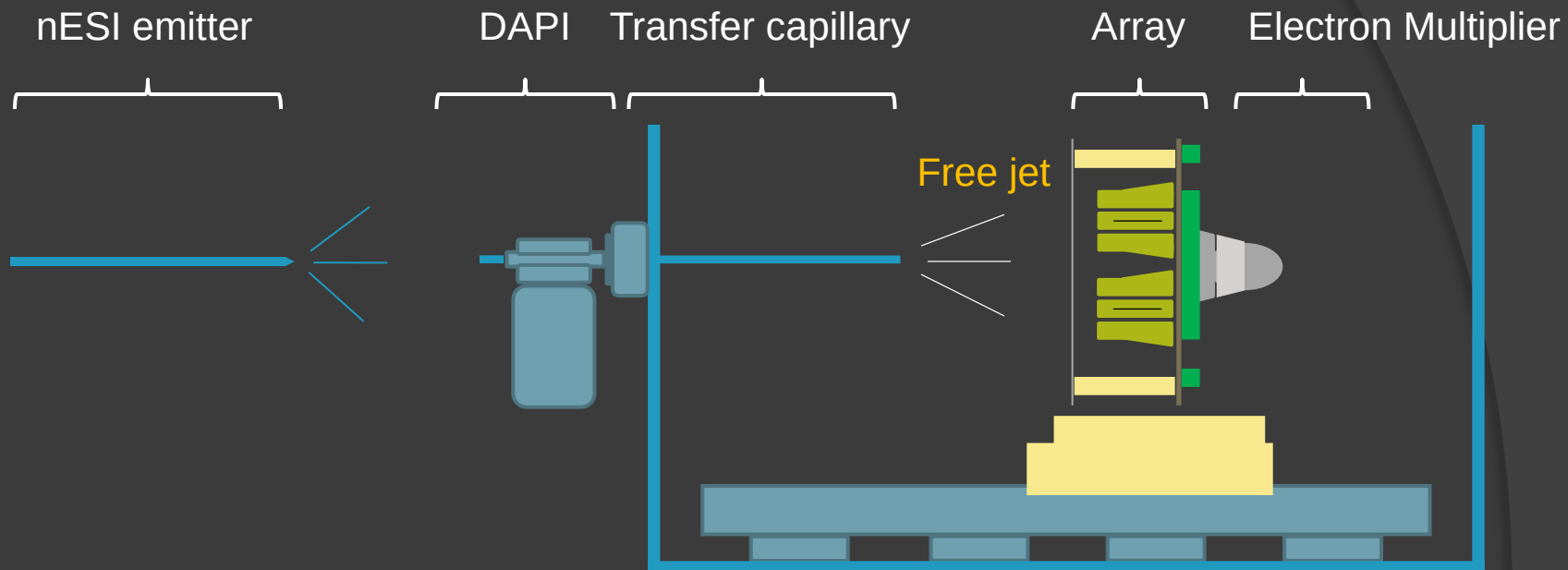


Monolithic, fully integrated  
**Additive Process**  
analyzer

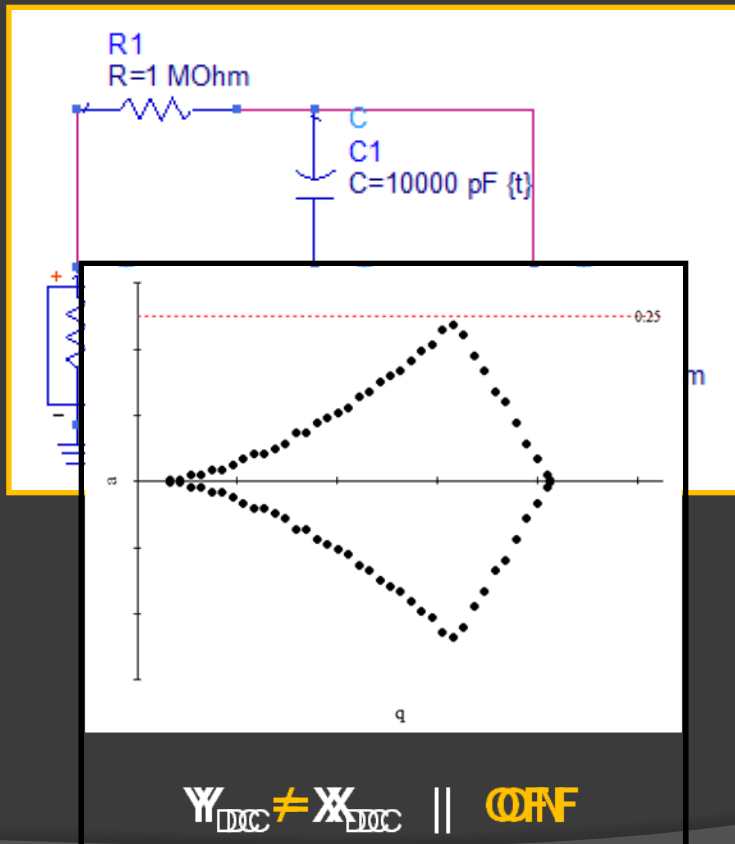
Flexible placement of  
electrodes & connections

Laser ablation used for  
electrode isolation

# Array Operation and Control

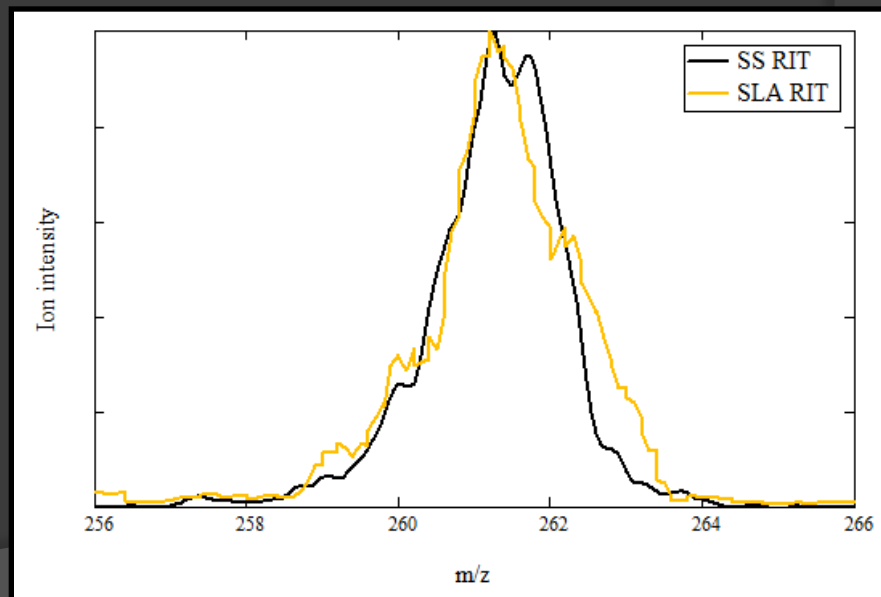
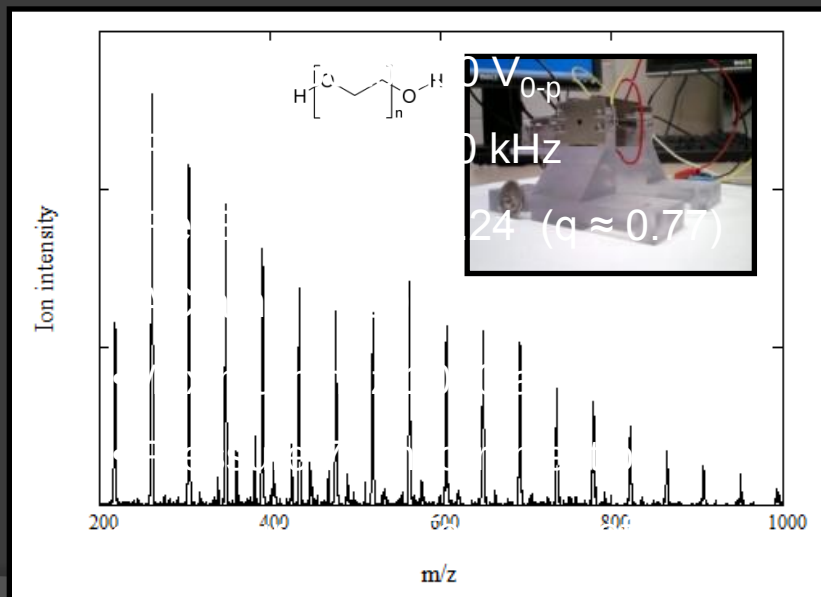
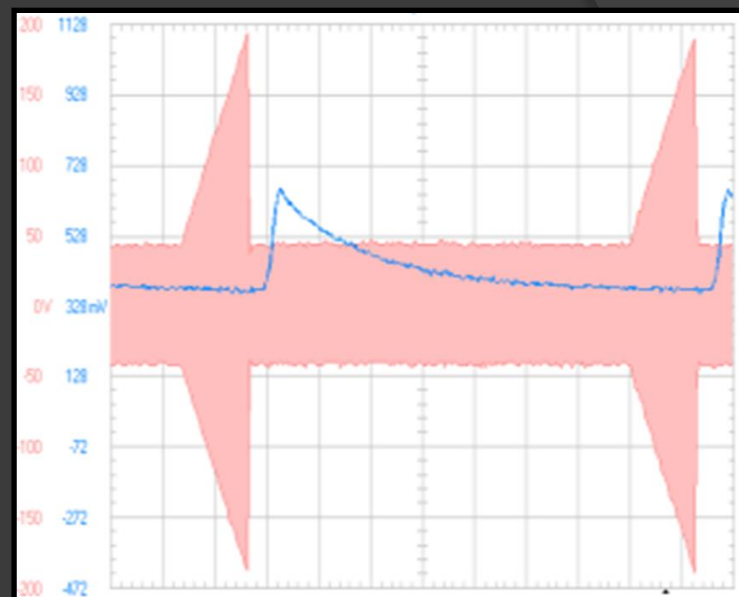
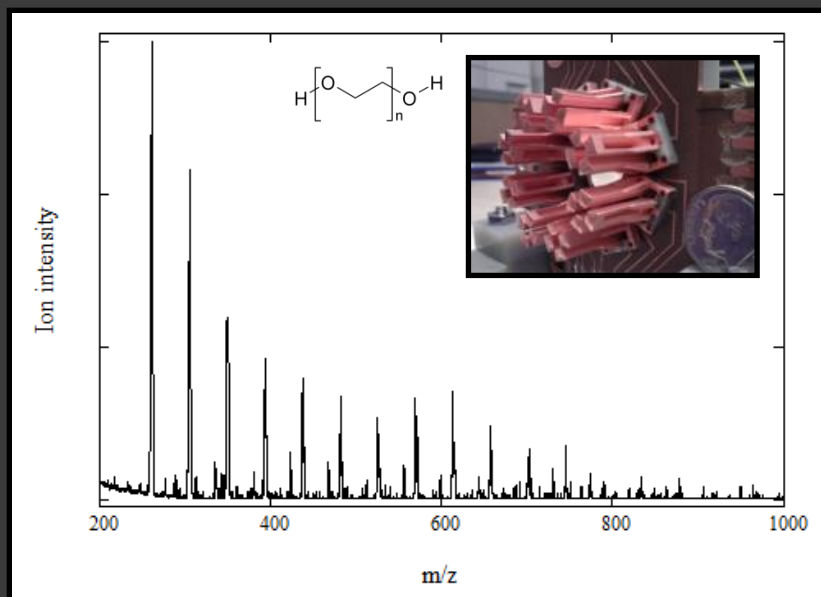


# Array Operation and Control: Bias Tee as a On & Off Switch

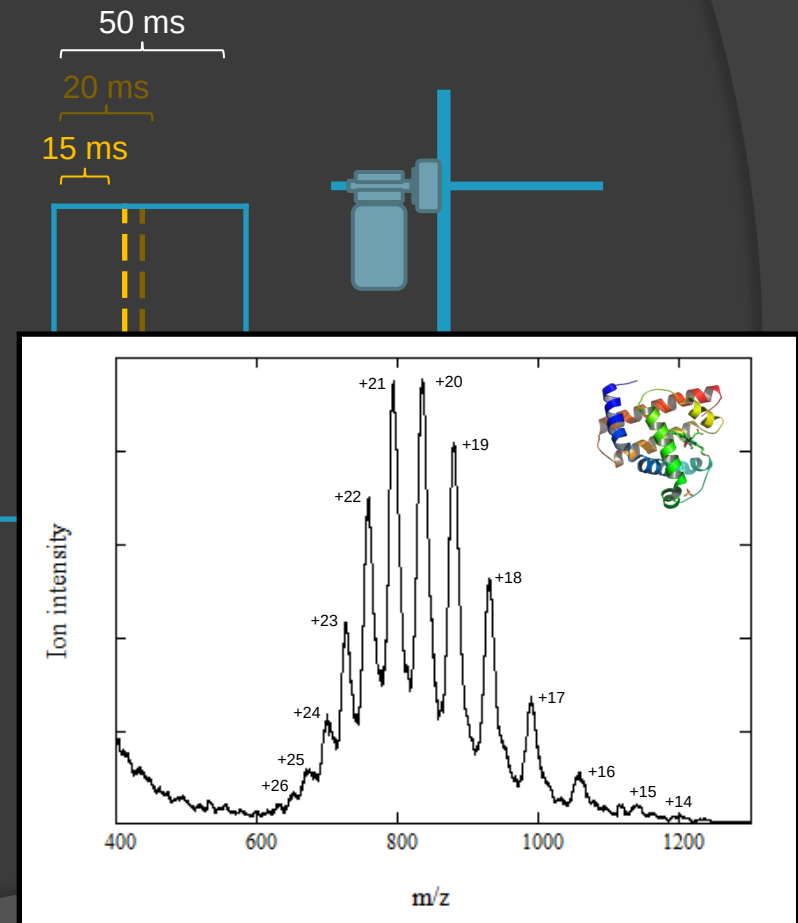
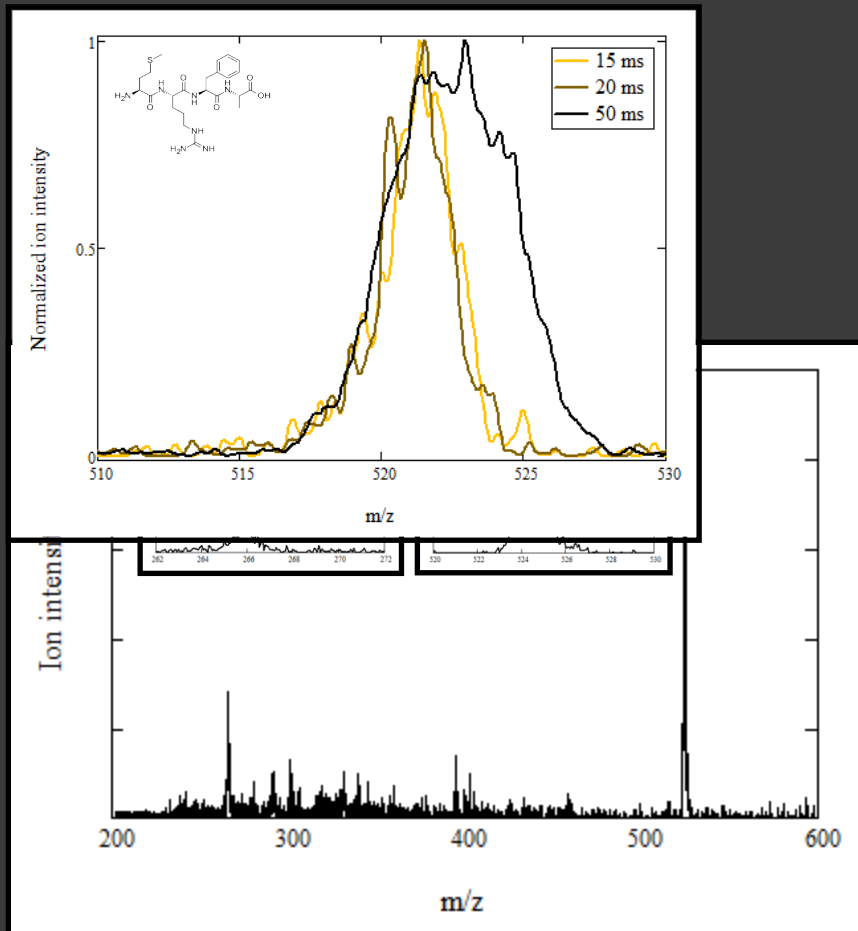


- Selective ion trap(s) operation inside the array
- Fast, reversible, and outside the vacuum chamber
- No physical obstruction to ion injection or detection
- RF voltages applied to all traps in the array

# Performance: Full scan MS (SLA vs. SS RIT)

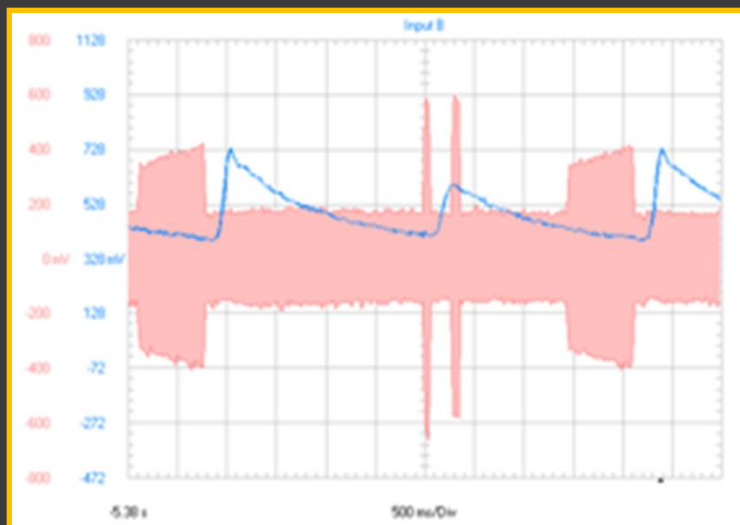


## Performance: Ion injection control, best resolution, and Intact protein analysis

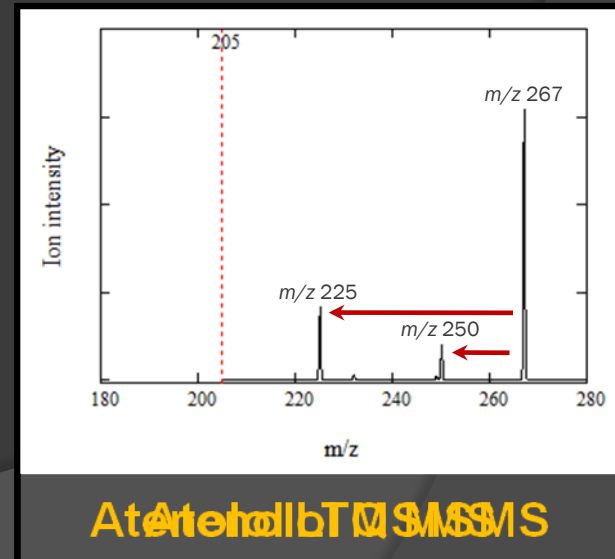
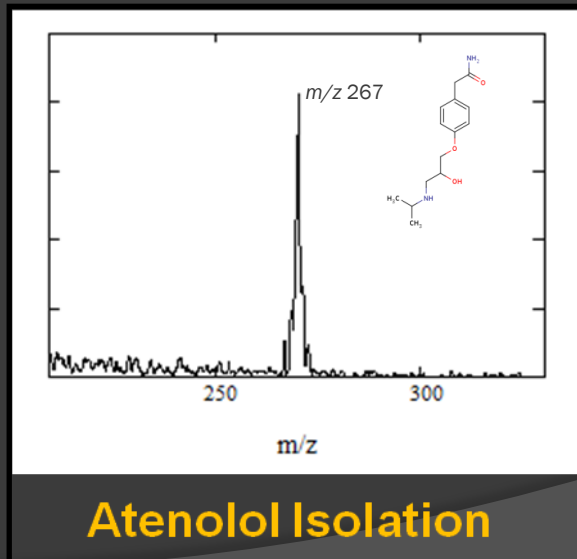
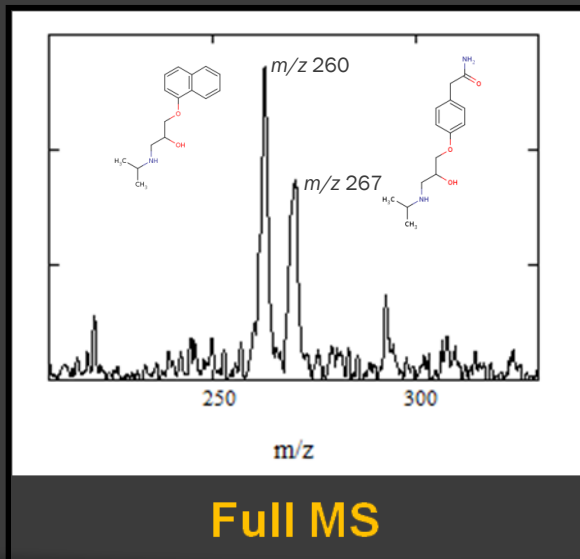




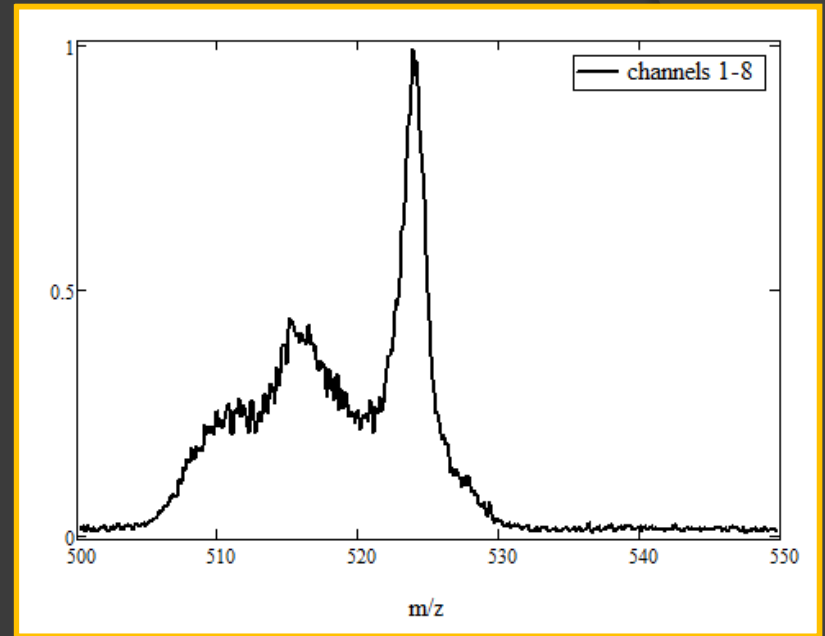
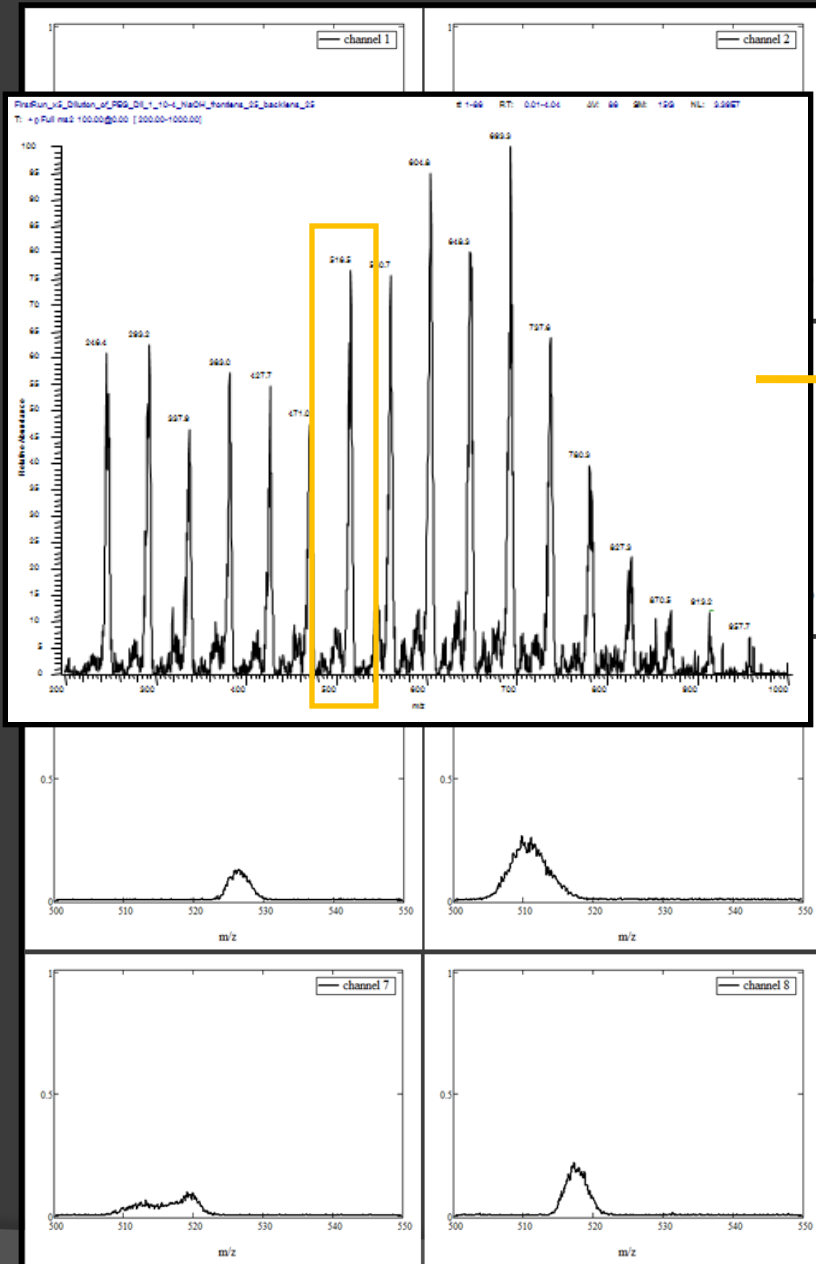
# Performance: Tandem MS of atenolol, double DAPI, Full, Isolation, and MS2



isolation q: 0.434  
 SWIFT notch: 148.7 to 154.9  
 isolation time: 75 ms  
 ion cooling time: 1750 ms  
 activation q: 0.655  
 activation time: 30 ms  
 activation amp:  $\sim 1 V_{p-p}$   
 DAPI time: 30 ms  
 KVDAC: 1.68 Vdc  
 dDAPI time: 10 ms

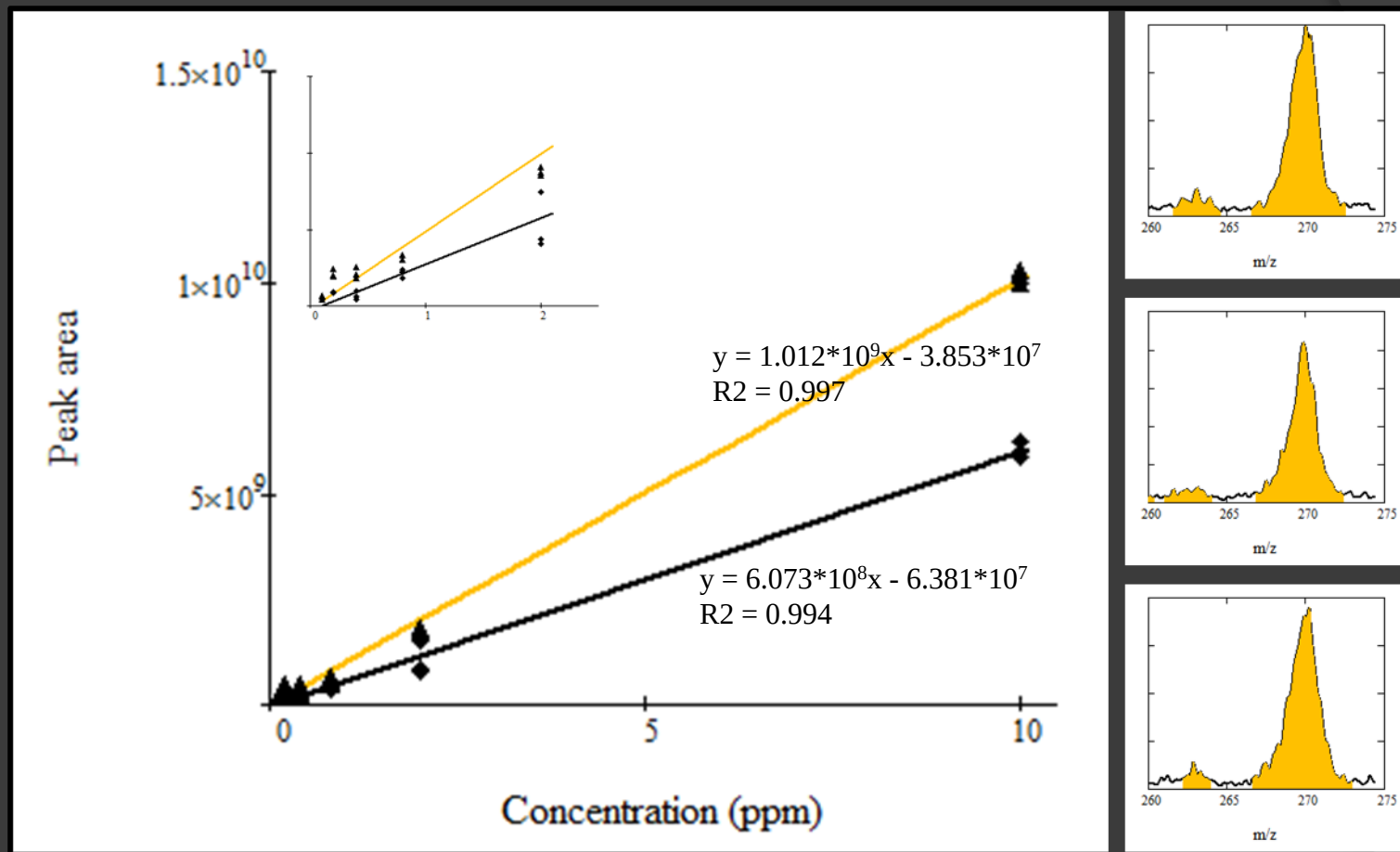


# Multi-channel data: All eight channels



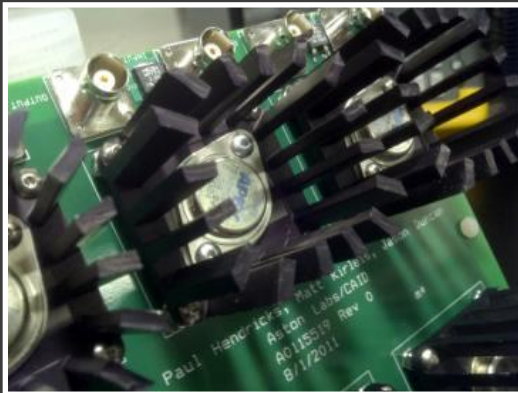
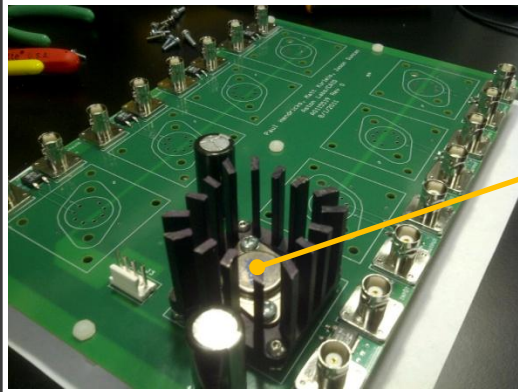
- RF voltages applied to all traps during analysis
- Primary cause of mass shift due  $\Delta r_0$
- Ejection occurs at a  $\Delta \sim 5 V_{0-p}$  for same  $m/z$
- $\Delta r_0$  of  $\sim 10$ s of  $\mu\text{m}$  between adjacent traps
- Compensate using individual RF drives

## Multi-channel data: Response for multiple vs. single channel

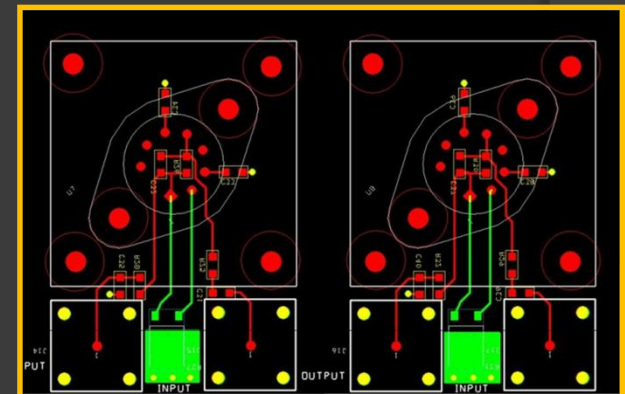
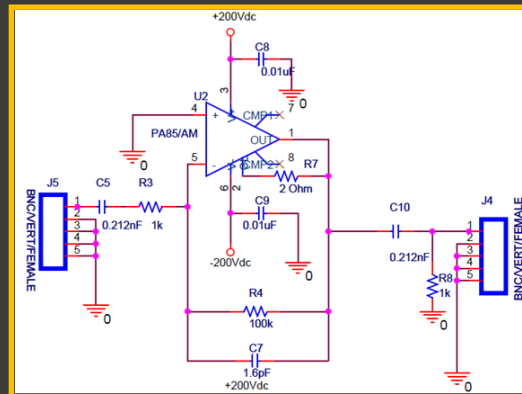


- 0.1  $\mu\text{m/ml}$  to 10  $\mu\text{g/ml}$  dynamic range
- Increased sensitivity & dynamic range with multiple channels
- Development of custom peak detection algorithm
- Peak widths for combined channels 2 – 2.5 amu without RF compensation

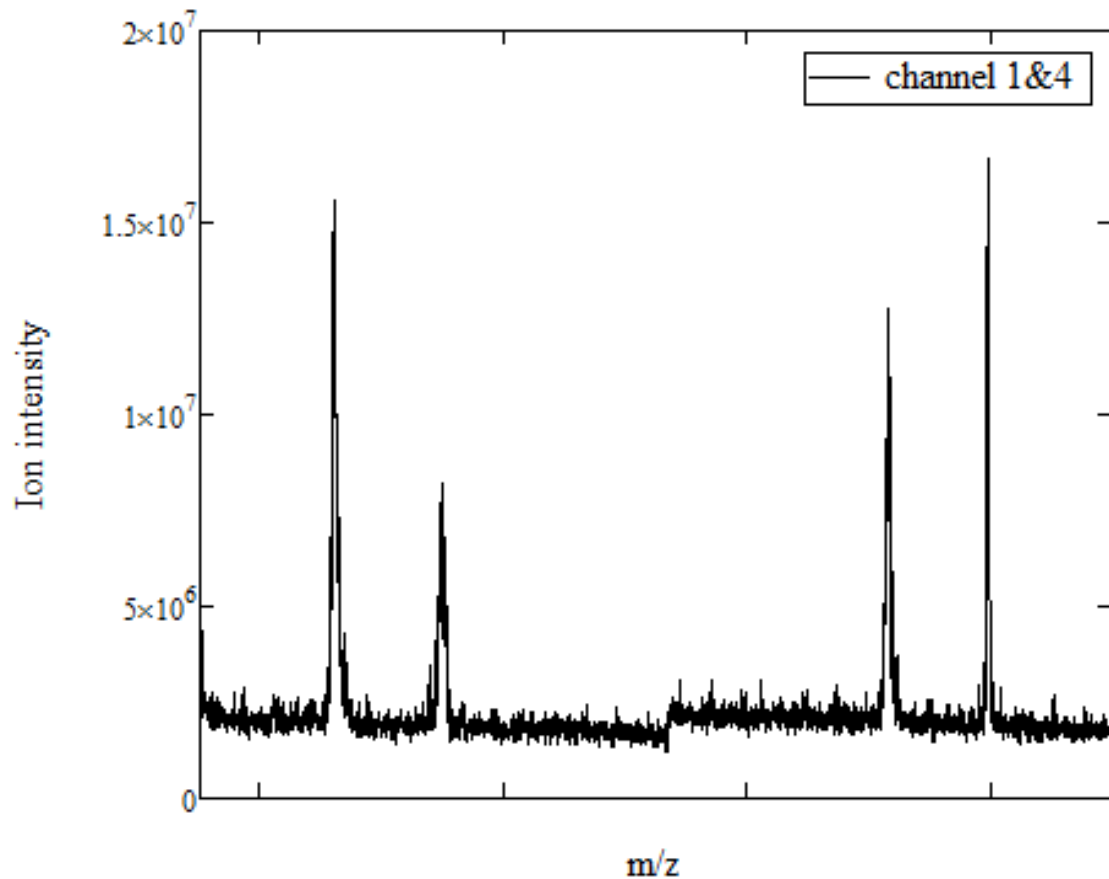
# Multi-channel RF drive: High Performance Operational Amplifiers



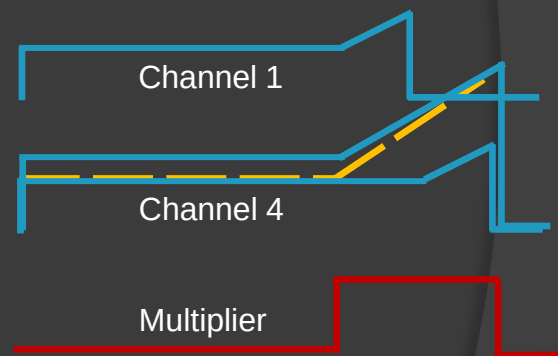
- Independent RF for each ion trap in the array
- Apex PA85 operational amplifier
- 450 V<sub>p-p</sub> output maximum voltage
- 1000 V/ $\mu$ s slew rate
- Anticipate maximum m/z 500 at 950 kHz
- Cost effective to produce 4 layer PCB



# Multi-channel RF drive: Fun with Independent RF Control

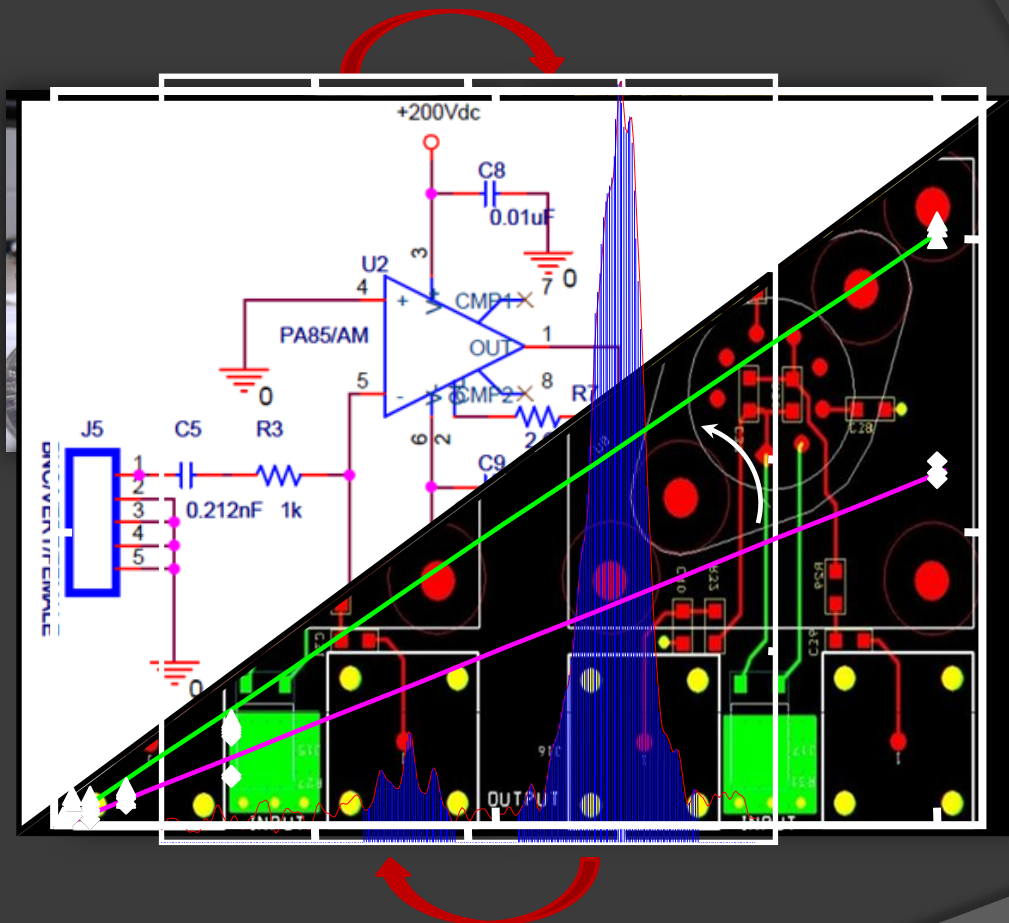


- *N,N*-Diethyl-3-methylbenzamide
- Overlapping voltage of channel 1 relative to 4





# Combined technology: Ion trap array design, fabrication, and control electronics



# Acknowledgements



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# Questions

# SLA Fabrication: Build Process and Laser Ablation



Ion Trap Build Process



Laser Ablation: Electrode Isolation